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APPLICANT
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U.S. PATENT DOCUMENTS

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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

PHM	Boning, Duane et al. "A Run-by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.
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PHM	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187th Meeting of the Electrochemical Society.</i> May 1995.
PHM	Moynes, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.
PHM	Moynes, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology.</i> 1995.
	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."
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	Khan, Karimullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan.</i> pp. 1 - 6.
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	Kim, Jiyoung et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>
EXAMINER	DATE CONSIDERED
PHM	11/8/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

* - Not considered because NO publication date was provided.